

Study of V-O and Cr-O films by x-ray photoelectron spectroscopy

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Some vanadium-oxygen materials such as VO₂ undergo metal-insulator transitions. This process is often followed by sudden change in magnetic properties at a critical temperature. The metal-insulator transition temperature of VO₂ is slightly above room temperature [1]. This transition is accompanied by a structural transition from a low temperature monoclinic phase to a high temperature rutile phase, and sharp increase in resistivity by 10³ to 10⁴ times. Due to this property, VO₂ is used in IR sensors and thermal-shield glass coating. CrO₂ is a ferromagnetic half metal which means it behaves as a metal for majority spins and as an insulator for minority spins. This property suggests applications as sensors because one can achieve very large resistance changes in magnetoresistance sensors for parallel and anti-parallel spin configurations.

Metal oxides like V-O and Cr-O can be grown on substrates such as TiO₂ and the growth mode influences the physical properties [2]. Samples are grown using CVD method using CrO₃ as precursor on a TiO₂ substrate. The aim of this investigation is to study the properties of V-O and Cr-O films on TiO₂ substrates using X-ray Photoelectron Spectroscopy (XPS) [3, 4, 5]. We will use the Kratos AXIS 165 Multitechnique Electron Spectrometer for our study. XPS is a quantitative spectroscopic technique that analyses the average surface chemistry of the topmost layers of a sample up to a depth of few nanometers. This technique determines the elemental composition, atomic concentrations and chemical states of elements present in the selvage region of a surface.

References

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